CLAIMS

[Claim 1]

A remover composition for ruthenium which remains on a substrate, wherein

the pH at 25 °C is equal to or above 8, and the composition comprises 1.0 to 2.0 weight % of one or more pH buffering ingredient(s) and periodic acid or a salt thereof.

[Claim 2]

The remover composition according to Claim 1, wherein the pH of the composition at 25 °C is equal to or above 8 and below 11.

[Claim 3]

The remover composition according to Claim 1 or 2, wherein the pH buffering ingredient(s) is(are) one or more selected from the group consisting of boric acid, borate, phosphoric acid, phosphate and bicarbonate.

~~[Claim 4]~~

~~The remover composition according to any one of Claims 1 to 3, comprising from 0.1 to 5.0 weight % of the pH buffering ingredient(s).~~

~~[Claim 5]~~

~~The remover composition according to any one of Claims 1 to 4, comprising an oxidizing agent that does not comprise a metal element, and comprising no oxidizing agent that comprises a metal element.~~

~~[Claim 6]~~

~~The remover composition according to Claim 5, wherein the oxidizing agent that does not comprise a metal element is an iodine compound.~~

~~[Claim 7]~~

~~The remover composition according to Claim 6, wherein the iodine compound is periodic acid or a salt thereof.~~

[Claim ~~8~~4]

The remover composition according to any one of Claims 1-3~~7~~, wherein the periodic acid or a salt thereof is one or more selected from the group consisting of ortho-periodic acid, sodium ortho-periodate, meta-periodic acid and sodium meta-periodate.

[Claim ~~9~~5]

The remover composition according to any one of Claims ~~6~~ 1 to ~~8~~4, comprising from 1.0 to 10.0 weight % of the periodic acid or a salt thereof ~~iodine compound~~.

[Claim ~~10~~6]

The remover composition according to any one of Claims 1 to ~~9~~5, wherein the remover composition is an aqueous solution.

[Claim ~~11~~7]

A method of removing ruthenium which remains on a substrate using the remover composition according to any one of Claims 1 to ~~10~~6.

[Claim ~~12~~8]

A method of removing ruthenium which remains on a substrate while suppressing the generation of ruthenium tetroxide using a remover composition comprising 1.0 to 2.0 weight % of one or more pH buffering ingredient(s) and the periodic acid or a salt thereof ~~one or more iodine compound(s)~~ and having pH equal to or above 8 at 25 °C.

~~[Claim 13]~~

~~The method according to Claim 12, wherein the remover composition further comprises one or more pH buffering ingredient(s).~~